

This listing of claims will replace all prior versions, and listings, of claims in the application.

LISTING OF CLAIMS

1-8. (canceled).

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9. (currently amended) An image detector for an x-ray image, comprising:
a luminophore layer;
a protective layer made of a polymer with a one-piece layer structure lying
over the luminophore layer, the protective layer being hardened
10 only in a region not abutting the luminophore layer.

10. (previously presented) The image detector according to claim 9, further comprising a non-hardened region that abuts the luminophore layer that is at least 5 μm thick.

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11. (previously presented) The image detector according to claim 9, wherein the hardened region that does not abut the luminophore layer is at least 3 μm thick.

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12. (previously presented) The image detector according to claim 9, wherein the hardened region of the protective layer is an electron-beam-treatment hardened region.

13. (currently amended) The image detector according to claim 9, wherein the protective layer is comprised of poly-para-xylylene poly-para-xylylene.

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14. (previously presented) The image detector according to claim 9, wherein the luminophore layer is a needle image plate.

15. (previously presented) The image detector according to claim 9, wherein the luminophore layer is comprised of alkali halogenides or alkaline earth halogenides.

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16. (currently amended) The image detector according to claim 15, wherein the luminophore layer is comprised of CsBr:Eu, BaFBr:Eu ~~BaFBr:Eu~~, RbBr:Tl, CsBr:Ga, CsI:Na or CsI:Tl.

10 17. (currently amended) A method for producing a polymer protective layer on an image detector for an x-ray image that comprises a luminophore layer, the method comprising:

vapor-depositing the protective layer made of a polymer and having a one-piece layer structure on the luminophore layer; and

15 hardening only a region of the protective layer that does not abut the luminophore layer.

18. (previously presented) The method according to claim 17, wherein a region with a thickness of at least 5 μm that abuts the luminophore layer is not
20 hardened.

19. (previously presented) The method according to claim 17, wherein a region that does not abut the luminophore layer and that is hardened is at least 3 μm thick.

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20. (previously presented) The method according to claim 17, wherein the hardening ensues via electron beam treatment.

21. (previously presented) The method according to claim 17, further comprising pre-treating the luminophore layer via a plasma treatment prior to the vapor-depositing of the protective layer.